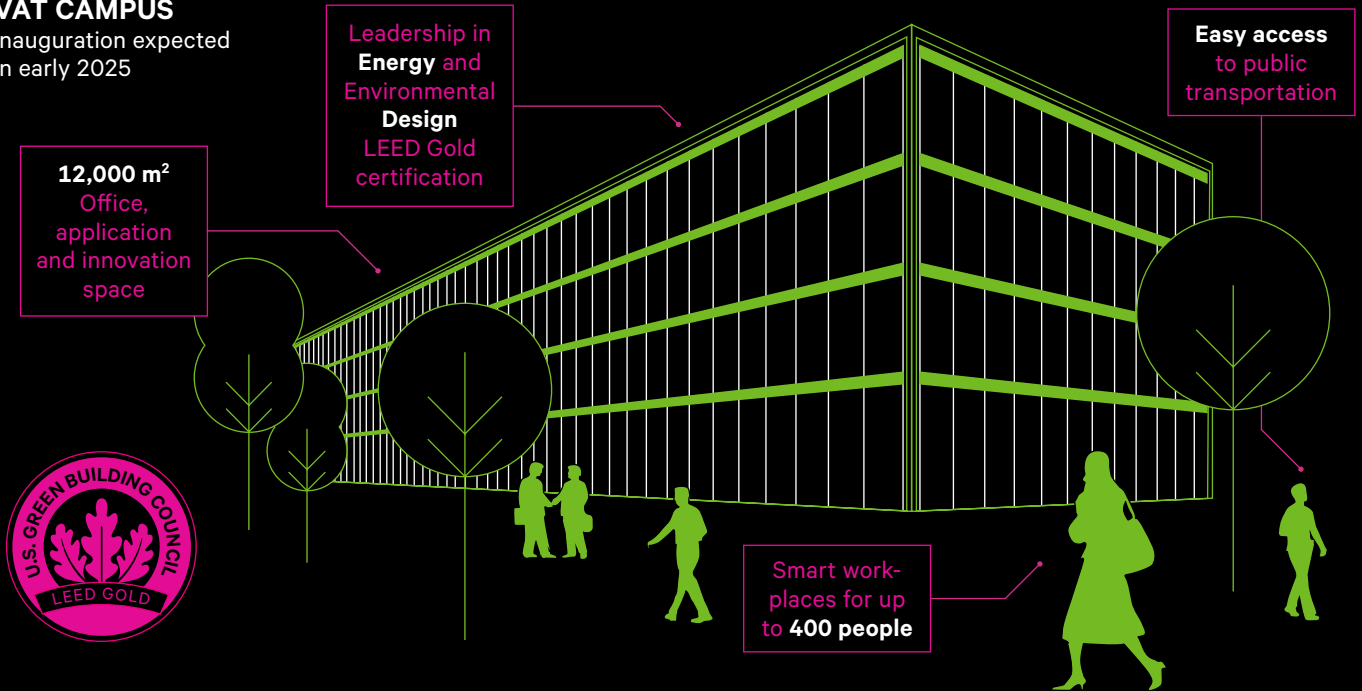


INNOVATION – INVESTING INTO FUTURE SUCCESS

The new Innovation Center represents the heart of VAT's innovation engine. Building on 60 years of innovation heritage, it is designed to accelerate our customer-centric innovation, drive global collaboration and fast development cycles to increase the speed to market for leading-edge vacuum solutions.

VAT CAMPUS

inauguration expected in early 2025



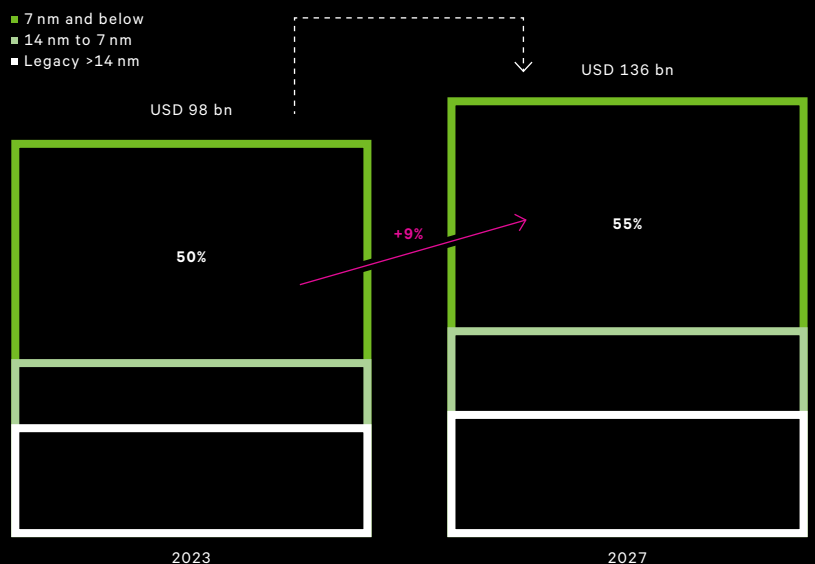
RECORD R&D INVESTMENTS

in CHF million



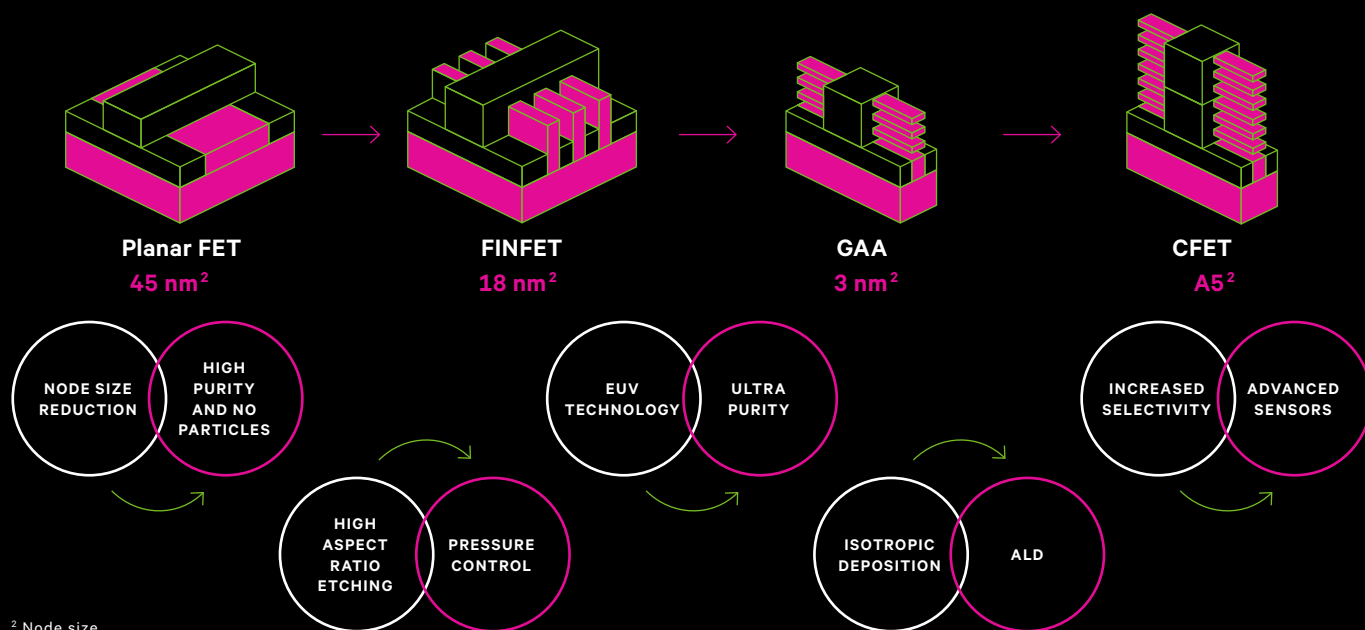
SMALLER NODES REQUIRE MOST ADVANCED VALVES

Share of Wafer Fab Equipment spend by node size ¹



Investing in future technologies and pushing the boundaries for vacuum applications for nearly 60 years is one key success factor of VAT.

TECHNOLOGY INFLECTIONS DRIVE VAT'S INNOVATION



² Node size

INNOVATION FOR TOMORROW'S INDUSTRY CHALLENGES



PRECISION DELIVERY ALD Valve

Atomic Layer Deposition (ALD) processes are required to fill the nanometric gaps with high precision across the wafer. They require high speed valves to manage process gas flows with a repeatability in the order of a millisecond.

PROCESS CONTROL Microelectromechanical Systems (MEMS)

Future leading edge chip manufacturing processes will require advanced pressure controls. VAT's MEMS technology allows

the integration of new types of pressure sensors, bringing our control valves to the next performance level.

